

Session Title:

11. Understanding and Addressing Instabilities of TFTs

Session Date:

August 21 (Wed.), 2024

Session Time:

10:50-12:10

Session Room:

Room C (Samda)

[C11-1] [Invited]

10:50-11:15

TBA

Toshio Kamiya (Tokyo Inst. of Tech., Japan)

[C11-2] [Invited]

11:15-11:40

Oxide-TFT Technology for Next-Generation Sustainable Electronics

Kenji Nomura (Univ. of California San Diego, USA)

[C11-3]

11:40-11:55

Analysis of Instability Mechanism under the High Voltage Drain Stress in Oxide Thin Film Transistors

Hyeonjoo Seul, Jaeyoon Park, Dongyeon Kang, Won-Sang Ryu, Jiyong Noh, and Kwon-Shik Park (LG Display Co., Ltd., Korea)

[C11-4]

11:55-12:10

Development of Highly Reliable Oxide TFTs for Display Applications Operating under Harsh Environment

Minho Lee, Hochang Lee, Hyun-cheol Cho, JungHyun Lee, Chan-Yong Jeong, DaeHwan Kim, Jiyong Noh, Kwon-Shik Park, and SooYoung Yoon (LG Display Co., Ltd., Korea)